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Characterization of microstructural defects in melt grown ZnO single crystals

W. Anwand,1,a) G. Brauer,1 R. I. Grynszpan,1 T. E. Cowan,1 D. Schulz,2 D. Klimm,2
J. Cižek,3 J. Kuriplach,3 I. Prochážka,3 C. C. Ling,4 A. B. Djurišić,4 V. Klemm,5
G. Schreiber,5 and D. Rafaja6

1Institut für Strahlenphysik, Helmholtz-Zentrum Dresden-Rossendorf, Postfach 510119, D-01314 Dresden, Germany
2Department of Low Temperature Physics, Faculty of Mathematics and Physics, Charles University, V Holešovičkách 2, CZ-180 00 Prague, Czech Republic
3Department of Physics, University of Hong Kong, Pokfulam Road, Hong Kong, People’s Republic of China
4Institute of Materials Science, TU Bergakademie Freiberg, Gustav-Zeuner-Str. 5, D-09599 Freiberg, Germany
5Institut für Strahlenphysik, Helmholtz-Zentrum Dresden-Rossendorf, Postfach 510119, D-01314 Dresden, Germany
6Institute of Materials Science, TU Bergakademie Freiberg, Gustav-Zeuner-Str. 5, D-09599 Freiberg, Germany

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Various nominally undoped, hydrothermally or melt grown (MG) ZnO single crystals have been investigated by standard positron lifetime measurements. Furthermore, optical transmission measurements and structural characterizations have been performed; the content of hydrogen in the bound state was determined by nuclear reaction analysis. A positron lifetime of 165–167 ps, measured for a brownish MG ZnO sample containing (0.30 ± 0.03) at.% of bound hydrogen, matches perfectly the value found for colorless MG ZnO crystals. The edge shift, observed in the “blue light domain” of the optical absorption for the former sample with respect to the latter samples, is estimated to be 0.70 eV, and found equal to a value reported previously. The possible role of zinc interstitials is considered and discussed. Microstructure analysis by X-ray diffraction and transmission electron microscopy revealed the presence of stacking faults in MG crystals in a high concentration, which suggests these defects to be responsible for the observed positron lifetime.

I. INTRODUCTION

Differences in the physical properties of ZnO crystals reported in the scientific literature are mainly related to the native defects formed during crystal growth.1–4 Recently, the effect of the microstructure defects on the electronic properties was investigated by means of positron annihilation spectroscopy (PAS) that employed either the standard22Na source technique3,6 or a variable positron energy beam.7,8

A systematic PAS study9 of various, nominally undoped, ZnO single crystals revealed the single positron lifetimes of 180–182 ps in crystals that were hydrothermally grown (HTG) and 165–167 ps in crystals that were grown from the melt (MG). In all crystals, a high concentration of hydrogen in a bound state (at least 0.3 at.%-%) has been detected by nuclear reaction analysis (NRA). The concentration of other impurities was low, as detected by inductively coupled plasma mass spectrometry (ICP-MS).

From ab initio calculations9 it has been inferred that the saturation trapping at \( V_{\text{Zn}} + 1H \) defects is the most natural explanation for the 180–182 ps positron lifetime observed in HTG crystals. Conversely, it has been concluded that the \( V_{\text{Zn}} + 2H \) and \( V_{\text{Zn}} + 3H \) defects do not trap positrons, and thus they cannot explain the 165–167 ps positron lifetime found in all MG crystals investigated so far. It is possible that structurally more complicated H-vacancy complexes might explain the measured lifetime. However, relevant ab initio calculations are not straightforwardly achievable.

All our HTG and MG crystals investigated previously by PAS9 were colorless and transparent in their as-received state. However, the researchers from the IKZ Berlin10 reported that their MG crystals had a color ranging from orange to brownish, and exhibited a large number of micrometer-sized precipitates visible even by optical microscopy. While the chemical nature of these precipitates could not be revealed, they tended to vanish after annealing at 900 °C in ambient air for 18 h and the crystals became almost colorless. Thus, a next consequential task was to investigate if precipitates or other possible microstructure defects, like stacking faults, exist in a sufficiently large concentration to be able to cause saturation trapping of positrons in MG crystals and hence to provide a more solid alternative explanation for the occurrence of the 165–167 ps lifetime.

To verify this hypothesis positron lifetime measurements were performed on such a pair of MG crystals of brownish color.10 These measurements were complemented by ICP-MS analysis to determine the content of impurities. In addition, to account for the possible influence of hydrogen on the ZnO properties - currently debated in the literature11–17 - the actual H content in this crystal was estimated by NRA.

These results, and those of additional optical transmission measurements, were then used for comparison with those obtained for colorless and transparent HTG and MG crystals studied previously.9

Furthermore, the possible role of zinc interstitials is considered and discussed. Finally, X-ray diffraction (XRD) and transmission electron microscopy (TEM) were performed to

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a)Electronic mail: w.anwand@hzdr.de.
assess the microstructure of the samples and to clarify the presence of stacking faults in MG crystals in particular.

II. EXPERIMENTAL

Single crystals of typical dimensions of \(10 \times 10 \times 0.5\) mm\(^3\) used here have been investigated previously. HTG samples were supplied by MaTecK GmbH (Jüllich) (MT-06, MT-08), with their O-face polished. MG crystals originated from Cermet Inc. (Atlantic-GA) (CM-06) and IKZ (Berlin) (B12, B13). The crystals from Cermet Inc., were grown without using a crucible and the IKZ crystals by using the Bridgman method. A pair of MG crystals from the same boule (B5) having brownish color has been supplied by IKZ (Berlin).

ICP-MS was performed using a Perkin-Elmer ELAN-9000 spectrometer. The possibility to determine the H content by standard NRA using 6.64 MeV \(^{15}\)N ions has already been successfully demonstrated for HTG ZnO nanorods and for HTG and MG ZnO crystals in connection with SRIM calculations ("The Stopping and Range of Ions in Matter" - software). A straggling (depth resolution) of \(\sim 5\) nm at a depth of \(\sim 100\) nm guarantees a negligible influence of surface contaminations. The amount of H measured with a detection limit of \(\sim 200\) ppm is then assumed to represent volume properties.

The microstructure of the crystals B5, B13 and MT-08 has been investigated by using XRD and TEM. Overview XRD measurements were carried out on a conventional Bragg-Brentano diffractometer that was equipped with a sealed X-ray tube with a Cu anode and with a secondary curved graphite monochromator.

High-resolution XRD comprising reciprocal space mapping and sample scans (\(\Omega\) scans) was performed using a triple-crystal diffractometer equipped with a sealed X-ray tube with a Cu anode and with a (111) oriented Si monochromator located in the primary beam. The monochromator lets pass only the spectral line CuK\(_{\alpha}\) to the sample. The third crystal was a (111) oriented Si analyzer located in front of a scintillation detector. In the high-resolution mode, the size of the primary beam was reduced to \(1 \times 0.09\) mm\(^2\). Consequently, the irradiated area on the sample surface was approximately \(1 \times 0.30\) mm\(^2\) for the 002 and 104 reflections and \(1 \times 0.15\) mm\(^2\) for the 004 reflection.

TEM was performed on a transmission electron microscope JEM 2010 FEF from JEOL that was operated at 200 kV, with FEF meaning field emission gun (F) and omega energy filter (EF). The samples for TEM were prepared in the plan-view orientation. This means that the primary electron beam was parallel to the (001) direction of the crystal. The first step in the TEM sample preparation was mechanical prethinning that was followed by etching in an Ar ion beam.

The state-of-the-art positron lifetime (LT) measurements were performed at room temperature by a fast-fast spectrometer having a timing resolution of 160 ps (Ref. 23) and collecting \(\sim 10^7\) events per spectrum. A \(^{22}\)Na positron source (\(\sim 1.5\) MBq) deposited on a 2 \(\mu\)m thick Mylar foil has been used. This source was covered with two identically treated ZnO crystals that formed a sandwich. The positron source contribution in the LT spectra consisted of two weak components with lifetimes of \(\sim 368\) ps and \(\sim 1.5\) ns, and corresponding intensities of \(\sim 8\%\) and \(\sim 1\%\), respectively. Each LT spectrum has been decomposed using a maximum likelihood procedure described in detail elsewhere.

The optical transmission of all crystals was investigated at IKZ Berlin using a PerkinElmer Lambda 19 spectrometer equipped with a white light source (tungsten halogen lamp) and a grating monochromator. The optical transmission defined as the intensity ratio \(I/I_0\) was generally measured within the wavelength range 200-2500 nm. \(I_0\) refers to the primary intensity of the light source; \(I\) is the intensity of the light after passing through the crystal. The reflectivity of each crystal has been assumed to be independent of the wavelength in first approximation, i.e., no correction of the transmitted amounts of light has been made.

The optical transmission of one of the as-received B5 crystals was measured independently at Charles University, Prague within the limited wavelength range 340-850 nm using a Spekol spectrometer equipped with a white light source and a mesh monochromator. Again, no correction for the change of reflectivity with the wavelength was performed.

The optical transmission of HTG crystals supplied by MaTecK GmbH (Jüllich) (MT-04) was investigated in their as-received state and after irradiation by 10 MeV electrons. The irradiation doses were 1 and \(2 \times 10^{18}\) cm\(^{-2}\), respectively. During irradiation, water cooling ensured that the sample temperature never exceeded 100 °C. More information about the properties of MT-04 samples can be found in Ref. 25.

III. RESULTS AND DISCUSSION

A. ICP-MS, NRA and LT of B5 samples

The chemical composition and H content of all samples investigated is given in Table I. The relation between the atomic concentrations \((C_{\text{at}})\) estimated by ICP-MS and the volume concentrations \((C_{\text{vol}})\) is given by \(C_{\text{vol}} = C_{\text{at}}/\Omega\), where \(\Omega\) is the average volume per atom in the ZnO lattice. For the ZnO lattice parameters used in previous calculations, a value of \(\Omega = 11.91 \times 10^{-24}\) cm\(^3\) is obtained.

From SRIM it was found that the analyzing \(^{15}\)N ions lose their kinetic energy \(E\) with increasing penetration depth \(x\) mainly by electronic collisions \((dE/dx)_{\text{electronic}} = 2.52\) keV nm\(^{-1}\)), whereas the nuclear collision energy loss is about two orders of magnitude smaller \((dE/dx)_{\text{nuclear}} = 0.006\) keV nm\(^{-1}\)). The energy transfer to the crystal during the analysis can be sufficient to release a weekly bound hydrogen atom from its bonding site, so that it will be able to start diffusing. It is generally assumed that individual H atoms are too reactive to remain isolated and become bound again immediately, so that this diffusion should most likely take place in the form of H\(_2\) molecules. As this diffusing hydrogen is no longer available at the analysis stage there is a drop in concentration with increasing \(^{15}\)N fluence. Throughout this paper, this will be referred to as "unbound H" (H-u). Conversely, any H atom which is not moving during analysis, because the energy transfer is not sufficient to release it from its bonding site, will be called hereafter "bound H" (H-b). However, it has to be clearly stated that from NRA it...
is impossible to draw any conclusion on the kind of bonding of H atoms in the crystal.

In the as-received B5 sample, NRA results do not indicate the presence of H in the unbound state (H-u = 0), whereas its content in the bound state amounted to H-b = (0.30 ± 0.03) at.-%. This latter concentration seemed rather stable, since it remains the same after annealing at 500 °C in air for 1 h and after a subsequent storage of the sample at room temperature for a period of 93 days.

Interestingly, the LT measurements of the brownish sample pair B5 revealed an average single positron lifetime of (165.4 ± 0.3) ps, which matches perfectly the 165-167 ps positron lifetime found in all colorless MG crystals investigated previously (see Table II). Owing to the brownish color of B5 samples caused by the presence of precipitates of dimensions visible by optical microscopy, such a match of properties could not be expected at first glance.

**B. Optical transmission**

In order to obtain an overview of the optical transmission properties of HTG and MG crystals, samples have been investigated within the largest available wavelength range (200–2500 nm). Preliminary data of another B5 sample were taken directly from Ref. 10. Results are presented in Fig. 1.

The transmission of the as-received HTG sample MT-06 has its onset at a wavelength of ~380 nm; then it rises sharply with increasing wavelength to a maximum value of ~80% and continues to increase almost linearly up to ~85% at 2500 nm. At the chosen conditions for the electron irradiation of MT-04 samples, only atomic size defects should be produced, including mono-vacancies, interstitials and perhaps even di-vacancies.

The transmission is very similar to that of the as-received MT-06 sample, except in the wavelength range 400-800 nm, where the rise is less steep.

In contrast, the transmission of all as-received MG samples was different in two ways:

1. After the onset at ~380 nm, the rise is less steep than for sample MT-06; the maximum transmission was in the range 75-80%.

2. A continuously decreasing transmission was found in the wavelength range 800-2500 nm. This gradual decline in the optical transmission at wavelengths in excess of about 1000 nm is linked to the free carrier concentration, i.e., does not involve the type of point defects produced by electron irradiation.

The drop of transmission in the long wavelength region of the brownish sample B5 has been discussed to be connected with the concentration of free charge carriers too. However, the existence of free charge carriers might also be interpreted in terms of the Zn precipitate formation, which is extremely difficult to be proven directly from experiments.

Computer simulations in the framework of the Mie-Lorenz...
theory could be helpful but are neither easy nor straightforward to perform.

Although in Ref. it has been mentioned that wafers of a thickness of \( \sim 800 \) \( \mu \)m were prepared, it has not been possible to ascertain afterwards the true thickness of the older B5 sample from which the transmission has been published.

A new B5 sample has been ground from originally 940 \( \mu \)m to various smaller thicknesses (i.e., 740, 510, 410, and 375 \( \mu \)m, respectively, within a \( \pm 5 \) \( \mu \)m margin error) and polished again prior to the transmission measurements. Hence, five new transmission spectra became available for the B5 series [Fig. 2(a)], labeled hereafter according to their thickness.

The first striking feature is the shift of the \( \sim 500 \) nm edge displayed for the thinned sample series, best evidenced by the thickness dependence of the peak position of the transmission derivative [Fig. 2(b)]. Various procedures were tested to estimate the wavelength associated with each maximum (including fitting to Gaussian, power and lognormal functions); the Gaussian fit proved to be less sensitive to the considered wavelength range. Figure 3 displays the calculated values within the wavelength range 350-700 nm.

This approach revealed the following:

1. For the five known sample thicknesses (375, 410, 510, 740, and 940 \( \mu \)m), the shift of the transmission edge seems to follow a linear trend (intercept \( 492 \pm 6 \) nm, goodness of fit parameter 0.993). A similar fit is also found for the linear dependence of the wavelength square root on thickness (Fig. 3).

2. In both cases, for an infinitely thin sample thickness, the extrapolated wavelength corresponds to a photon energy of \( 2.52 \pm 0.03 \) eV.

3. The position of the maximum derivative around the transmission edge for the B5 sample investigated in Ref. seems to match (visually) that of the 940 \( \mu \)m thick sample [Fig. 2(b)]. Assuming that the linear dependence also holds for this sample, a thickness of 940 \( \pm 8 \) \( \mu \)m can then be extrapolated for the B5 sample investigated in Ref. 10 (see Fig. 3).

A possible explanation of the 500 nm edge shift resulting from the grinding of sample B5 could be the release of internal stresses with thinning, since a shift toward lower wavelengths with increasing annealing temperature (900 °C in ambient air for 18 h) has also been reported in Ref. 10. Conversely, the shift of this “blue edge” toward higher wavelengths with increasing fluence, i.e., due to defects induced by electron irradiation in MT-04 samples (Fig. 1), seems to substantiate such an explanation. Considering the bulk effect of such internal stresses, it sounds reasonable to expect an almost linear dependence of the edge shift on thickness.

Nonetheless, the spectra of B5 (Ref. 10) and new B5-940 samples exhibit slight differences despite their similar thickness. Indeed, an extra transmission edge seems to occur at around 900 nm for the former sample as opposed to the latter. This might be caused by their different microstructures, because both samples have been cut at different locations from the grown ZnO boule.

The transmission of one B5 sample has been measured in Prague within the wavelength range of 340–850 nm and found to be very similar to that published in Ref. 10.

From the plot of the squared absorption coefficient \( \alpha^2 \) versus photon energy \( E \), it is possible to obtain the optical bandgap energy \( E_g^{opt} \). This is based on the fact that in so-called direct bandgap semiconductors the joint density of states of electrons and holes gives the absorption coefficient \( \alpha \) which is initially proportional to \( (h^2 - E_g^{opt})^{1/2} \), as the conduction and valence bands are almost parabolic in the
vicious of the band edges, \(^{30}\) \(\hbar \nu\) being the photon energy. While this type of approach may be considered somewhat arbitrary, it has already been validated for GaAs (Ref. 31) and ZnO. \(^{32–36}\) Its application to the transmission data from Fig. 1 taken in the broadest wavelength range available (200–2500 nm) gave the results shown in Fig. 4.

For sample B5 a value of \(E_{\text{opt}}\) = (2.67 ± 0.12) eV was derived. The large error bar accounts for the uncertainty in defining a common slope to B5 (Ref. 10) and B5 (Prague measurement). This numerical value is close to the energy extrapolated for the transmission for the B5 sample series (Fig. 3). Indeed, within the blue edge domain, the product of the absorption coefficient \((x)\) by the thickness \((x)\) (i.e., the exponent of the transmission exponential factor) should be dimensionless. Therefore we expect \(x\) and \(x\) to follow a reciprocal dependence on energy, and intrinsic optical properties to prevail when the thickness tends to zero. The various \(E_{\text{opt}}\) values derived from this approach are collected in Table III together with values estimated in Refs. 32–36.

The difference between the nominal bandgap \(E_g = 3.37\) eV at 300 K known for ZnO (Refs. 1–3) and the \(E_{\text{opt}}\) values given in Table III indicates the presence of optically active defects in all samples. This means that the corresponding defects are characterized by this energetic amount from either the valence or conduction band within the bandgap.

In the case of the results presented in Ref. 32, the authors suggested formation of fluorine atoms substituting oxygen during growth, which results in fluorine atoms having the charge state \([+2]\). In Ref. 34, the authors concluded that oxygen vacancies \((V_O)\) were present, because they found in their ZnO films that \(E_{\text{opt}}\) decreases with increasing oxygen pressure during deposition.

For sample B5, \((E_g - E_{\text{opt}})\) yields a relatively large value of 0.70 eV. Indeed, such a value (\(~0.7\) eV) has already been reported\(^{37}\) from previous PAS investigations in combination with optical absorption studies. The corresponding shift of the optical absorption bandedge and the reddish color were thereby induced by annealing of ZnO crystals either in Zn or Ti vapor and concluded to be due to the formation of \(V_O\). A shift of the optical edge by 0.7 eV was discussed earlier by Halliburton et al. in Ref. 38. However, Ref. 37 linked the shift to oxygen vacancies and excluded zinc interstitials whereas Halliburton et al. in Ref. 38 could not draw this distinction.

The orange coloration of ZnO was attributed to the presence of \(V_O\) in Refs. 37 and 39, it was concluded that zinc interstitials (\(Zn_i\)) were not the donors in as-grown ZnO – rather, that an H atom trapped in \(V_O\), called the HO defect, \(^{40}\) forms multicenter bonds and thus acts as shallow donor. Furthermore, it is appealing to consider the disposition of \(Zn\) which can be present at high concentration in ZnO grown in Zn-rich conditions. In Ref. 41 it is assumed that these \(Zn\) defects form at octahedral lattice sites with a positive charge state \([+2]\) and with a formation energy of \(E_{\text{f}} = 0.87\) eV. Hence, it is reasonable to suppose that the light absorbers in sample B5 could also be finely dispersed \(Zn\) which then condense either in the form of nanometer-sized (diameter \(~3\) nm) metallic precipitates\(^{42}\) or by the generation of stacking faults (SF’s) characterized by an additional (0002) plane.\(^{43}\)

It is important to emphasize that the formation of a SF would require the precipitation of a double layer consisting of zinc and oxygen atoms. Thus, if only \(Zn\) occur in an excess concentration, oxygen atoms would have to diffuse from the surrounding lattice to form a complete (0002) double layer. As a consequence, a high concentration of \(V_O\) should be found in the vicinity of a SF. However, these defects might be ‘invisible’ to positrons because they form a HO defect, the occurrence of which has been extensively discussed in the literature\(^{13,40,44}\) and experimentally investigated (see for example, Refs. 15, 45 and 46 and references given therein). If the H atomic bond is strong enough so as not to be broken by energy transfer during NRA, its maximum concentration in the ZnO crystals can be estimated from the NRA results, which give the amount of H-b to be of the order 0.3 at.% or even higher.\(^{9}\)

The annealing of an optically transparent ZnO crystal grown by seeded chemical vapor transport in zinc vapor at 1100 °C for 30 min has been found to convert its color to deep red.\(^{38}\) The optical absorption edge was observed to shift from \(~400\) nm to \(~500\) nm, corresponding to a shift of the optical edge by 0.7 eV. The observed increase in the number

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<th>Growth Method</th>
<th>(E_{\text{opt}}/\text{eV})</th>
<th>Reference</th>
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<td>B12</td>
<td>Bridgman Method</td>
<td>3.16 ± 0.02</td>
<td>This work (Fig. 4)</td>
</tr>
<tr>
<td>B13</td>
<td>Bridgman Method</td>
<td>3.16 ± 0.02</td>
<td>This work (Fig. 4)</td>
</tr>
<tr>
<td>B5</td>
<td>Bridgman Method</td>
<td>2.52 ± 0.03</td>
<td>This work (Fig. 3)</td>
</tr>
<tr>
<td>B5</td>
<td>Bridgman Method</td>
<td>2.67 ± 0.12</td>
<td>This work (Fig. 4)</td>
</tr>
<tr>
<td>CM-06</td>
<td>Pressurized Melt Growth</td>
<td>3.17 ± 0.03</td>
<td>This work (Fig. 4)</td>
</tr>
<tr>
<td>MT-06</td>
<td>Hydrothermal Growth</td>
<td>3.17 ± 0.03</td>
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<td>ZnO crystal</td>
<td>Bridgman Method</td>
<td>3.21</td>
<td>32</td>
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<td>Sol-Gel Deposition</td>
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<td>Molecular Beam Epitaxy</td>
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</tr>
<tr>
<td>ZnO thin film</td>
<td>Magnetron Sputtering</td>
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<td>35</td>
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<tr>
<td>ZnO thin film</td>
<td>Spray Pyrolysis</td>
<td>3.26</td>
<td>36</td>
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</table>

TABLE III. Estimated \(E_{\text{opt}}\) values for various ZnO samples from this work and the literature (Refs. 32–36).
of free carriers was proposed to be a result of either (1) the formation of Znii or (2) having the ground state of the neutral VO near the conduction band. Interestingly, from this conclusion the coexistence of VO and Znii after coloration is not excluded.

It was suggested in another recent work\textsuperscript{47} that Znii and VO can coexist. The authors have shown that the interactions between defects lead to a significant reduction in their formation energies, if the concentration of intrinsic defects becomes sufficiently high in O-deficient ZnO. Hence, the formation of both VO and Znii becomes significantly enhanced by a strong attractive interaction between them, making these defects an important source of n-type conductivity in ZnO.

According to Ref. 37, Znii is not the cause of the coloration of ZnO but is most probably connected with the presence of VO\textsuperscript{37–39} which however is ‘invisible’ to positrons. On the other hand, Znii are not expected to be stable at room temperature but highly mobile (see Ref. 48 and references therein). Its disposition in ZnO crystals remains to be determined and one can only consider which configurations might eventually explain the positron lifetime of 165-167 ps observed both in colorless MG ZnO crystals\textsuperscript{9} and our brownish B5 sample. In our opinion, a possible complex formed between a Znii and a nitrogen atom replacing an oxygen atom in the crystal lattice (Znii - NO) (Ref. 49) is not capable of trapping a positron.

In a very recent work,\textsuperscript{46} HO were again identified as the color-changing defects in ZnO and the presence of Znii and VZn was ruled out. This finding is not in contradiction to the supposed existence of SF’s, which possibly might trap positrons and thus be able to explain the 165-167 ps positron lifetime. Hence, the SF’s are anticipated to exist in a sufficiently large concentration in MG ZnO crystals independent of their coloration. The difference between colorless and brownish crystals would thus be caused just by the VO or HO defects located at the SF.

C. Microstructure analysis using XRD and TEM

The main goals of the microstructure analysis were (1) to verify the presence of stacking faults that are expected to be capable of explaining the positron lifetime of 165-167 ps observed in MG samples and (2) to identify the differences in the microstructure of the MG and HTG samples that could be responsible for the differences in the positron lifetime and in the optical bandgap energy.

XRD measurements performed on MG samples (B5 and B13) confirmed their single-crystalline nature. No traces of crystalline Zn were found that could be regarded as a constituent of the precipitates, which were recognized by optical absorption (see Sec. III B). The only indicator of the existence of precipitates (of unknown chemical composition) is the intense diffuse scattering in the overview XRD pattern (Fig. 5). However, the diffuse scattering arises generally on strain fields in crystal lattices.

The differences in the microstructures of MG samples were found to be rather small. The analyzed volume of sample B13 consisted of two mosaic blocks having the mutual disorientation of approximately 0.27°. This disorientation was calculated from the distance of two distinct diffraction maxima observed along qx in the reciprocal space map of the diffraction line 002 (see Fig. 6). The angular scale was calculated into the components of the reciprocal space vectors (qx and qz) according to:

\[
q_x = \frac{2\pi}{\lambda} \left[ \cos(\Theta - \Omega) - \cos(\Theta + \Omega) \right] \\
q_z = \frac{2\pi}{\lambda} \left[ \sin(\Theta - \Omega) - \sin(\Theta + \Omega) \right]
\]

where \(\Theta\) is the Bragg angle of the diffraction line under consideration and \(\Omega\) the inclination of the sample from the symmetrical position. For a constant \(\Theta\) and a small difference in \(\Omega\), it follows from Eq. (1) that the distances in the angular space and in the reciprocal space are directly proportional to each other.
\[ \Delta q_x = \frac{2\pi}{\lambda} [\sin(\Theta - \Omega) + \sin(\Theta - \Omega)]\Delta\Omega \]  

(2)

According to Eq. (2), the above distance between the diffraction maxima \((\Delta\Omega = 0.27^\circ)\) corresponds to \(\Delta q_x = 0.0113 \text{ Å}^{-1}\) (cf. Fig. 6). In sample B5, no such disorientation was observed within the analyzed volume. The mean disorientation of lattice planes within individual mosaic blocks was below 60 arcsec in both MG samples as concluded from the full-widths at the half maximum (FWHM) of the reflections 002, 004 and 104, which were measured as \(\Omega\) scans (Fig. 7). However, as the FWHM recalculated into \(q_x\) do not change significantly with the length of the diffraction vector, the instrumental line broadening and natural width of the Darwin curve can be regarded as more probable reasons for the observed line broadening in the \(q_x\) direction than the microstructure defects.

On the contrary, the XRD line broadening measured in the MG samples along \(q_z\) increases with the size of the diffraction vector that indicates inhomogeneous changes of the interplanar spacing and consequently the presence of local lattice strains. Moreover, diffraction lines are strongly asymmetric in the \(q_x\) direction, which suggests that the sources of the inhomogeneous changes of the interplanar spacing are stacking faults.50

Another indicator of the presence of stacking faults, and their different density in the MG samples, is a slight difference in the lattice parameters determined for samples B5 and B13: \(a(B5) = 0.32530(2) \text{ nm}, c(B5) = 0.52069(2) \text{ nm}, a(B13) = 0.32571(2) \text{ nm}\) and \(c(B13) = 0.52057(2) \text{ nm}\). The elementary cell volumes determined from these lattice parameters also differ; the elementary cell of sample B5 \((47.72 \times 10^{-3} \text{ nm}^3)\) is smaller than that of sample B13 \((47.83 \times 10^{-3} \text{ nm}^3)\).

The extrapolation of the XRD line broadening to \(q_z = 0\) yielded FWHM \(\approx 36\) arcsec, which excludes any line broadening due to the size of the mosaic blocks. Local lattice strains that are related to the inhomogeneous changes of the interplanar spacing and that are anticipated to stem from the stacking faults are illustrated in the TEM micrograph given in Fig. 8. Moreover, Fig. 8 reveals a rough estimation of the density of these microstructure defects. However, one has to keep in mind that only microstructure defects with a certain orientation to the diffraction vector are visible for TEM.
performed in diffraction contrast. Thus, the real density of the microstructure defects is assumed to be higher than the defect density depicted in Fig. 8.

In the HTG sample (MT-08), a minor fraction of crystalline domains of ZnO with other orientations was found (Fig. 9). These small and almost randomly oriented crystallites fragmented the ZnO domains with the dominant crystallographic orientation. Thus, the effect of the crystallite size on the line broadening along qz could be seen in this particular sample. The estimated size of the domains with the dominant orientation was between 200 and 260 nm. Furthermore, the presence of differently oriented domains and the fragmentation of the crystal caused the highest diffuse scattering among the samples under study (Fig. 10). Sample MT-08 possesses the lattice parameter within the basal plane a = 0.32552(2) nm and the highest lattice parameter c among the samples under study, c = 0.52074(2) nm. The corresponding volume of the elementary cell is 47.79 × 10⁻³ nm³.

FIG. 10. Reciprocal space map taken for sample MT08 in the vicinity of the reciprocal lattice point 002. The intensities are plotted in logarithmic scale.

VI. CONCLUSIONS

Measurements of conventional positron lifetime and optical transmission of various nominally undoped, hydrothermally (HTG) or melt grown (MG) ZnO single crystals have been presented together with their structural characterizations by X-ray diffraction and transmission electron microscopy. In addition, the content of bound hydrogen (H-b) of a brownish MG ZnO single crystal (sample B5) has been estimated to H-b = (0.30 ± 0.03) at.-%.

The positron lifetime of the sample B5 was found to match perfectly the 165-167 ps positron lifetime of colorless MG ZnO crystals. Its optical absorption edge shift was estimated to be 0.70 eV, which is comparable with values reported previously in literature.¹⁰⁻¹²

The disposition of excess Zn₁, which can be present at high concentration in ZnO grown in Zn-rich conditions as discussed in the literature, has been summarized. As a result, it was proposed to investigate if SF's generally exist in a sufficiently large concentration in MG ZnO crystals to explain the 165-167 ps positron lifetime range observed.⁹

From careful, comparative XRD investigations it has been concluded that the presumed presence of Zn₁ in the form of nanometer-sized (diameter ~3 nm) metallic precipitates¹⁰ in the new brownish sample B5 is very unlikely, in contrast to another brownish sample from the same grown boule (B5).⁴² The only indicator of the existence of precipitates observed here was the intense diffuse scattering in the overview XRD pattern, which however could originate from the lattice strain fields in the vicinity of the anticipated SF's.

The combined discussion of XRD and TEM analyses led to the conclusion that SF's are present in MG crystals in high concentrations, which suggests that this defect be responsible for the observed positron lifetime of 165-167 ps. The difference from the positron lifetime observed in HTG ZnO crystals [180-182 ps (Ref. 9)] is understandable because SF's represent two-dimensional positron traps which usually exhibit shorter positron lifetimes than real open volume defects including Vz₁ + 1H complexes. Positrons are attracted to SF's due to their lowered atomic density compared to the bulk material.

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